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By: *Linda E. Hastings*

LINDA E. HASTINGS

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Attorney Docket No.:NEKW14.868

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Inventor: KAICHIRO NAKANO, ET AL.

Serial No.: 09/036,219

Filed: March 6, 1998

Title: **CHEMICALLY AMPLIFIED RESIST LARGE IN TRANSPARENCY AND SENSITIVITY TO EXPOSURE LIGHT LESS THAN 248 NANOMETER WAVELENGTH AND PROCESS OF FORMING MASK**

Examiner: J. Chu

Group Art Unit: 1752

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February 27, 2001

Assistant Commissioner for Patents  
Washington, D.C. 20231

**SUB-POWER OF ATTORNEY**

S I R :

I, Samson Helfgott, Reg. No. 23,072, attorney of record herein, do hereby grant a sub-power of attorney to Linda S. Chan, Reg. No. 42,400, Michael I. Markowitz, Reg. No. 30,659 and Harris A. Wolin, Reg. No. 39,432 to act and sign in my behalf in the above-referenced application.

Respectfully submitted,

*[Signature]*  
\_\_\_\_\_  
Samson Helfgott  
Reg. No. 23,072

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